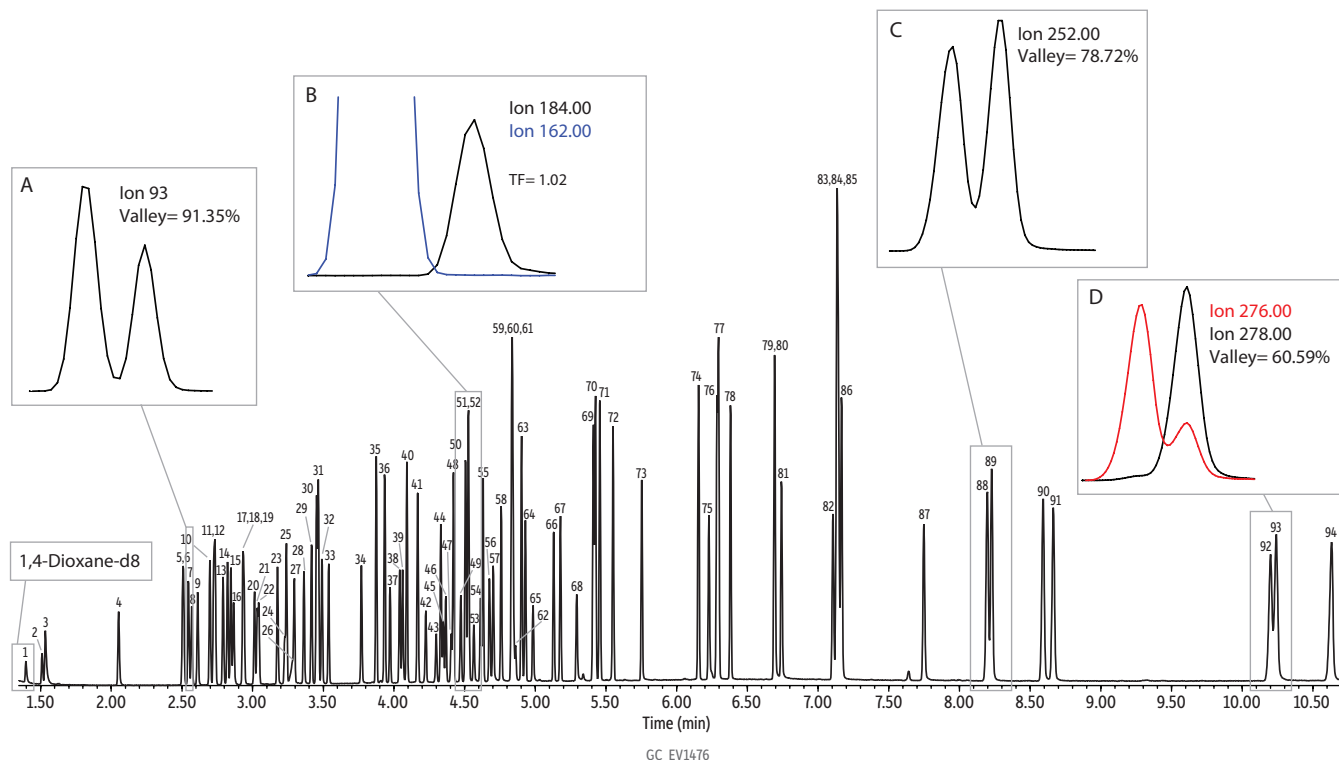


Semivolatiles on Rxi-5Sil MS by U.S. EPA Method 8270 Using the GC Accelerator Kit and Split Injection with a 120 V GC Oven



GC_EV1476

Peaks	tR (min)	Peaks	tR (min)	Peaks	tR (min)
1. 1,4-Dioxane-d8 (IS)	1.40	33. Hexachlorobutadiene	3.54	65. 2,4,6-Tribromophenol (SS)	4.98
2. N-Nitrosodimethylamine	1.51	34. 4-Chloro-3-methylphenol	3.77	66. 4-Bromophenyl phenyl ether	5.13
3. Pyridine	1.53	35. 2-Methylnaphthalene	3.87	67. Hexachlorobenzene	5.18
4. 2-Fluorophenol (SS)	2.05	36. 1-Methylnaphthalene	3.93	68. Pentachlorophenol	5.29
5. Phenol-d6 (SS)	2.51	37. Hexachlorocyclopentadiene	3.97	69. Phenanthrene-d10 (IS)	5.41
6. Phenol	2.51	38. 2,4,6-Trichlorophenol	4.04	70. Phenanthrene	5.43
7. Aniline	2.55	39. 2,4,5-Trichlorophenol	4.06	71. Anthracene	5.46
8. Bis(2-chloroethyl) ether	2.57	40. 2-Fluorobiphenyl (SS)	4.09	72. Carbazole	5.55
9. 2-Chlorophenol	2.61	41. 2-Chloronaphthalene	4.17	73. di-n-Butyl phthalate	5.75
10. 1,3-Dichlorobenzene	2.70	42. 2-Nitroaniline	4.23	74. Fluoranthene	6.15
11. 1,4-Dichlorobenzene-d4 (IS)	2.73	43. 1,4-Dinitrobenzene	4.30	75. Benzidine	6.23
12. 1,4-Dichlorobenzene	2.74	44. Dimethyl phthalate	4.33	76. Pyrene-d10 (SS)	6.28
13. Benzyl alcohol	2.79	45. 1,3-Dinitrobenzene	4.35	77. Pyrene	6.30
14. 1,2-Dichlorobenzene	2.82	46. 2,6-Dinitrotoluene	4.37	78. p-Terphenyl-d14 (SS)	6.38
15. 2-Methylphenol	2.85	47. 1,2-Dinitrobenzene	4.41	79. 3,3'-Dimethylbenzidine	6.69
16. Bis(2-chloroisopropyl)ether	2.87	48. Acenaphthylene	4.42	80. Butyl benzyl phthalate	6.69
17. 4-Methylphenol	2.93	49. 3-Nitroaniline	4.47	81. Bis(2-ethylhexyl) adipate	6.74
18. 3-Methylphenol	2.93	50. Acenaphthene-d10 (SS)	4.51	82. 3,3'-Dichlorobenzidine	7.11
19. N-Nitrosodi-N-propylamine	2.94	51. Acenaphthene	4.53	83. Bis(2-ethylhexyl) phthalate	7.13
20. Hexachloroethane	3.01	52. 2,4-Dinitrophenol	4.53	84. Chrysene-d12 (IS)	7.14
21. Nitrobenzene-d5 (SS)	3.03	53. 4-Nitrophenol	4.56	85. Benz[a]anthracene	7.14
22. Nitrobenzene	3.04	54. 2,4-Dinitrotoluene	4.61	86. Chrysene	7.17
23. Isophorone	3.18	55. Dibenzofuran	4.63	87. Di-n-octyl phthalate	7.75
24. 2-Nitrophenol	3.23	56. 2,3,5,6-Tetrachlorophenol	4.68	88. Benzo[b]fluoranthene	8.20
25. 2,4-Dimethylphenol	3.24	57. 2,3,4,6-Tetrachlorophenol	4.70	89. Benzo[k]fluoranthene	8.23
26. Benzoic acid	3.28	58. Diethyl phthalate	4.76	90. Benzo[a]pyrene	8.59
27. Bis(2-chloroethoxy)methane	3.30	59. 4-Chlorophenyl phenyl ether	4.83	91. Perylene-d12 (IS)	8.67
28. 2,4-Dichlorophenol	3.36	60. Fluorene	4.84	92. Indeno[1,2,3-cd]pyrene	10.20
29. 1,2,4-Trichlorobenzene	3.42	61. 4-Nitroaniline	4.85	93. Dibenz[a,h]anthracene	10.24
30. Naphthalene-d8 (IS)	3.45	62. 4,6-Dinitro-2-methylphenol	4.86	94. Benzo[ghi]perylene	10.63
31. Naphthalene	3.47	63. N-Nitrosodiphenylamine (as diphenylamine)	4.90		
32. 4-Chloroaniline	3.49	64. Diphenylhydrazine (as azobenzene)	4.93		

Column Rxi-5Sil MS, 20 m, 0.15 mm ID, 0.15 µm (cat.# 43816)
Sample 8270 MegaMix (cat.# 31850), 8270 Benzidines mix (cat.# 31852)
 Benzoic acid (cat.# 31879), Revised B/N surrogate mix (cat.# 31888)
 Acid surrogate mix (4/89 SOW) (cat.# 31063)
 Revised SV internal standard mix (cat.# 31886)

Diluent: Methylene chloride
Conc.: 20 µg/mL (IS/SS 20 µg/mL)

Injection
Inj. Vol.: 1 µL split (split ratio 20:1)
Liner: Topaz 4 mm single taper w/wool (cat.# 23303)
Inj. Temp.: 275 °C

Oven
Oven Temp.: 60 °C (hold 0.7 min) to 285 °C at 39.8 °C/min to 305 °C at 4.3 °C/min to 330 °C at 28.5 °C/min (hold 3.5 min)

Carrier Gas He, constant flow
Flow Rate: 0.72 mL/min

Detector MS
Mode: Scan
Transfer Line Temp.: 280 °C
Analyzer Type: Quadrupole
Source Temp.: 330 °C
Quad Temp.: 180 °C
Electron Energy: 70 eV
Solvent Delay Time: 1.3 min
Tune Type: DFTPP
Ionization Mode: EI
Scan Range: 39-550 amu
Scan Rate: 9.8 scans/sec
Instrument Agilent 7890B GC & 5977A MSD
Notes Analyzed using a 120 V oven equipped with the GC Accelerator kit (cat.# 23849).



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